

IN THE SPECIFICATION:

On page 1, just below the title, please insert the following paragraph:

This application is the National Phase of PCT/NL2004/000876, filed December 16, 2004, which claims priority to Netherlands applications 1025094, filed December 21, 2003, and 1025096, filed December 22, 2003, the entire contents of all being incorporated herein by reference in their entireties.

On page 1, please amend the paragraph beginning in line 8 as follows:

According to the invention, a method for manufacturing a functional layer is provided, where a substrate is introduced into a process chamber, where at least one plasma is generated by at least one DC plasma cascade source, ~~such as for instance a plasma cascade source~~, where at least one deposition material is deposited on the substrate under the influence of the plasma, while, at the same time, at least one second material is applied to the substrate with the aid of a second deposition process, while the functional layer has no catalytic function.

On page 4, please amend the paragraph beginning in line 29 as follows:

The invention further relates to an apparatus for manufacturing a functional layer on a substrate, where the apparatus is provided with at least one DC plasma cascade source to generate at least one plasma, while the apparatus comprises means to introduce a first deposition material into each plasma, while the apparatus is further provided with substrate positioning means for bringing and/or keeping at least a part of a substrate in such a position in a process chamber that the substrate contacts the plasma, while the apparatus is provided with a second deposition source, which second deposition source is arranged to deposit at least one second deposition material on the substrate at the same time as the plasma cascade source, while the functional layer is no catalytically active layer.